

**Objective to use  $\text{Al(OH)}_3$**  : To produce a solution of ALPO -  $\text{Al}_2\text{O}_3\text{-}_{3x}(\text{PO}_4)_{2x}$

**Solution synthesis :**

Materials to be used –  $\text{Al(OH)}_3$ , HCl,  $\text{H}_3\text{PO}_4$

By products : HCl,  $\text{H}_2\text{O}$

**Post-process :**

- i. ALPO to be spin-coated on Si/ $\text{SiO}_2$ /ITO substrate at room temperature.
- ii. Annealing upto 1200 C in furnace.
- iii. Aluminum deposition on film by Thermal Evaporator.
- iv. Proxima IV measurement of thus produced Si/ $\text{SiO}_2$ /ITO/ALPO/Al Device.